

Fourth Triennial Special Issue on Images in Plasma Science

IMAGES convey a wealth of information in a compelling manner that can last a lifetime. Just as many people carry images in their minds of pleasant events in their lives, images conveying scientific meaning also remain in our memories. By their very nature, plasma phenomena are incredibly rich and complex. As our ability to design experiments and models has improved, the data they produce can become a torrent of information that is challenging to present and appreciate using traditional means. To address this challenge, we have seen an explosion in the use of imagery to convey large amounts of data in a manner that fosters deeper understanding in a short period of time. Beyond their value as communication tools, many of the images are clearly works of art in their own right. As scientists, we take pride in conveying the results of our work and often toil for hours optimizing the presentation to tell the story that we want to tell.

It is our pleasure to present to you the "Fourth Triennial special issue on Images in Plasma Science." The purpose of the special issue is to highlight physically significant plasma phenomena through the aesthetics of images and visualization. The popularity of the special issue continues to grow with this issue

containing nearly 200 unique images of plasma phenomena, encompassing the entire spectrum of plasma sources, pressure regimes and applications. The criteria for accepting contributions to the special issue were that they not only discuss a significant physics issue, but also that the images be aesthetically pleasing. It is our hope that the special issue will serve as an introduction for the general public and nonexperts to the imagery of plasmas, and in doing so, pique their interest in the science and technology of ionized gases.

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